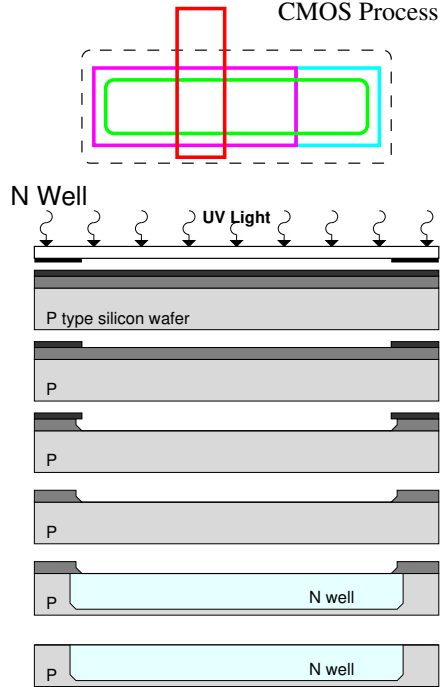


PMOS Enhancement transistor CMOS Process



many steps for a single mask

Active Area



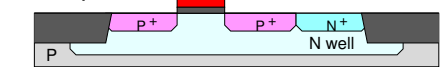
Polysilicon



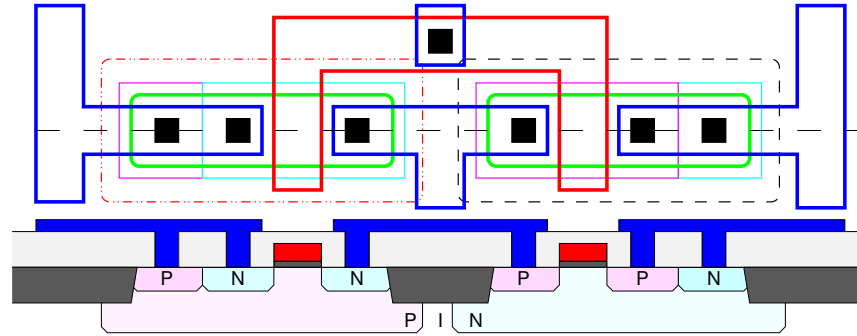
P+ Implant



N+ Implant



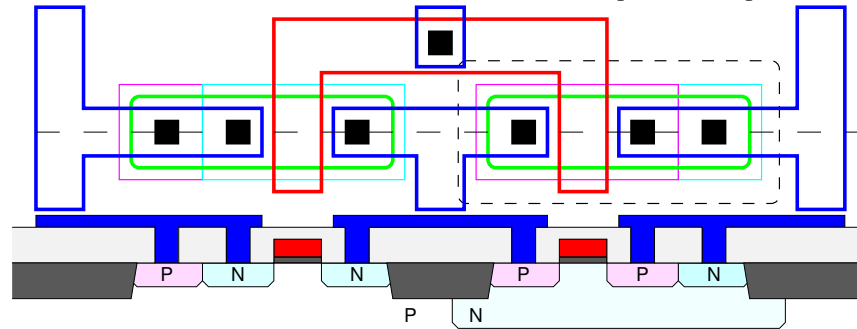
CMOS Inverter



Twin Tub CMOS Process

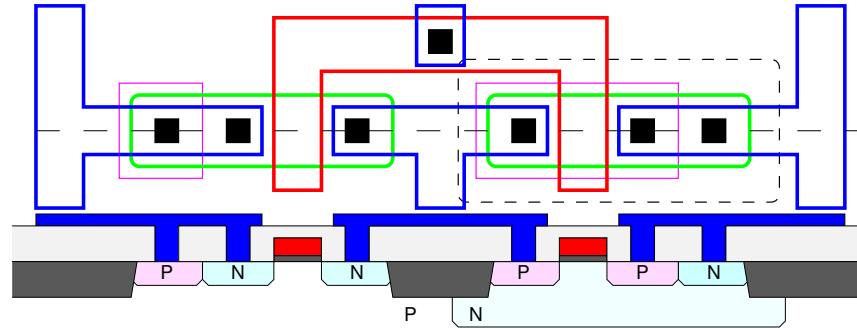
CMOS Inverter

N-Well CMOS Process (with explicit N+ implant mask)



CMOS Inverter

N-Well CMOS Process (without explicit N+ implant mask)



Features may be determined by a number of masks
e.g. NMOS source drain: ActiveArea AND NOT(NWell OR Poly OR PImplant)